US00D907593S

(12) **United States Design Patent**
Nunomura et al.

(10) **Patent No.: US D907,593 S**
(45) **Date of Patent: ** Jan. 12, 2021**

(54) **DISCHARGE CHAMBER FOR A PLASMA PROCESSING APPARATUS**

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(73) Assignee: **Hitachi High-Tech Corporation**, Tokyo (JP)

(**) Term: **15 Years**

(21) Appl. No.: **29/611,001**

(22) Filed: **Jul. 18, 2017**

(30) **Foreign Application Priority Data**

Jan. 20, 2017 (JP) 2017-000807

(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/184**

(58) **Field of Classification Search**
USPC D9/500, 516, 519, 535, 544, 738, 741; D24/108, 207, 210, 216, 222, 224, 229,
(Continued)

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Assistant Examiner — Fritzgerald L Butac
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(57) **CLAIM**

The ornamental design for a discharge chamber for a plasma processing apparatus, as shown and described.

DESCRIPTION

This application contains subject matter related to the following co-pending U.S. design patent applications: Application No. 29/610,995, filed herewith and entitled "Electrode Cover for a Plasma Processing Apparatus"; Application No. 29/610,996, filed herewith and entitled "Electrode Cover for a Plasma Processing Apparatus"; Application No. 29/610,998, filed herewith and entitled "Ring for a Plasma Processing Apparatus"; and Application No. 29/610,999, filed herewith and entitled "Cover Ring for a Plasma Processing Apparatus".

FIG. **1** is a front and left side perspective view of a discharge chamber for a plasma processing apparatus according to the design;

FIG. **2** is a front elevational view thereof;

FIG. **3** is a left side elevational view thereof;

FIG. **4** is a right side elevational view thereof;

FIG. **5** is a rear elevational view of a discharge chamber for a plasma processing apparatus, rotated 180°;

FIG. **6** is a top plan view thereof;

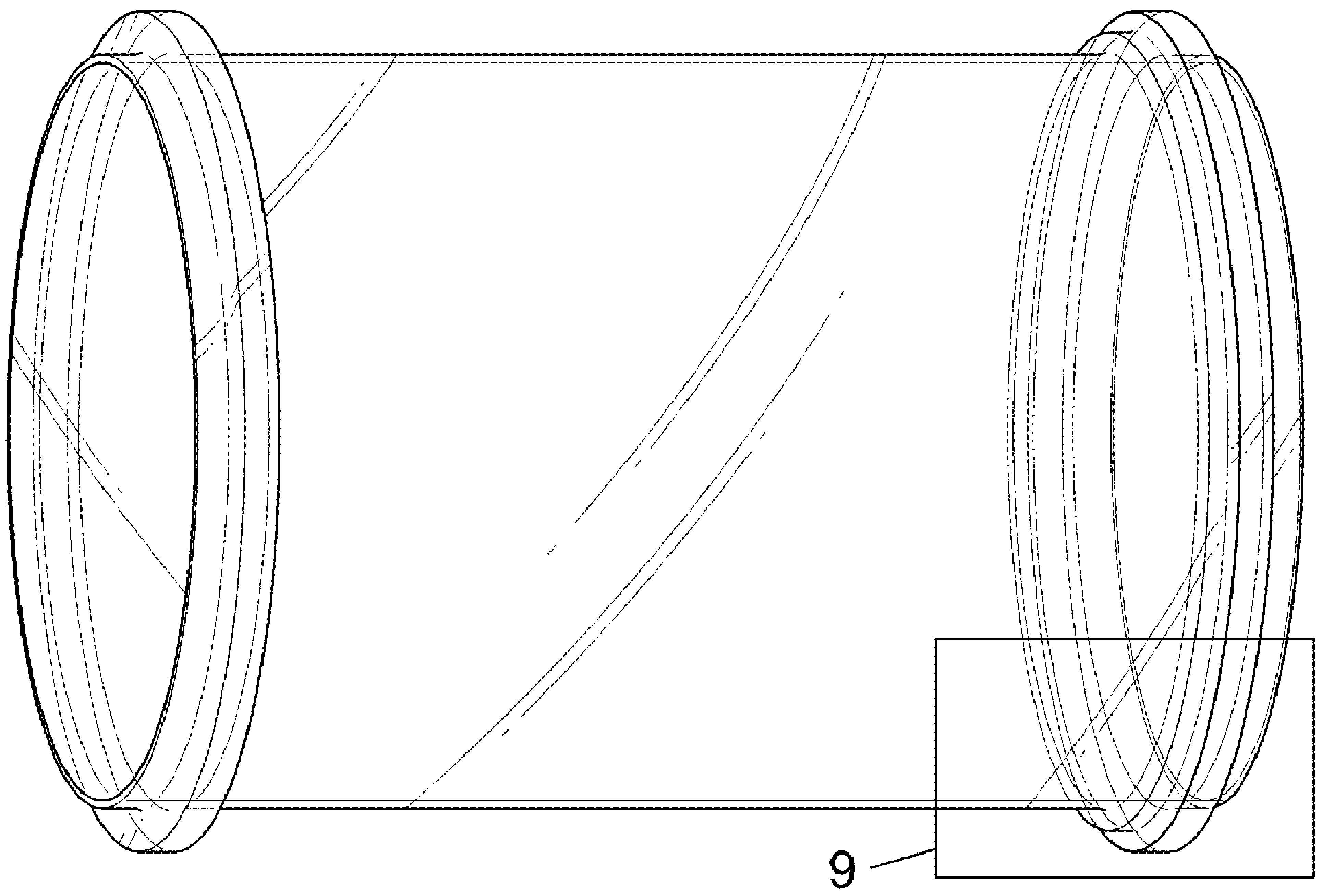
FIG. **7** is a bottom plan view of a discharge chamber for a plasma processing apparatus, rotated 180°;

FIG. **8** is a cross-sectional view taken along line **8**-**8** of FIG. **2**;

FIG. **9** is an enlarged view of the portion shown in BOX **9** in FIG. **1**; and,

FIG. **10** is an enlarged view of the portion shown in BOX **10** in FIG. **8**.

1 Claim, 5 Drawing Sheets



(58) **Field of Classification Search**
USPC D24/231, 232; D26/9, 11, 93, 104, 105, D26/110, 113, 114, 117; D15/150; D13/101, 118, 158, 160, 173, 177, 178, D13/179, 180, 182, 184, 199
CPC H01J 37/32431; H01J 37/32935; H05H 1/0081
See application file for complete search history.

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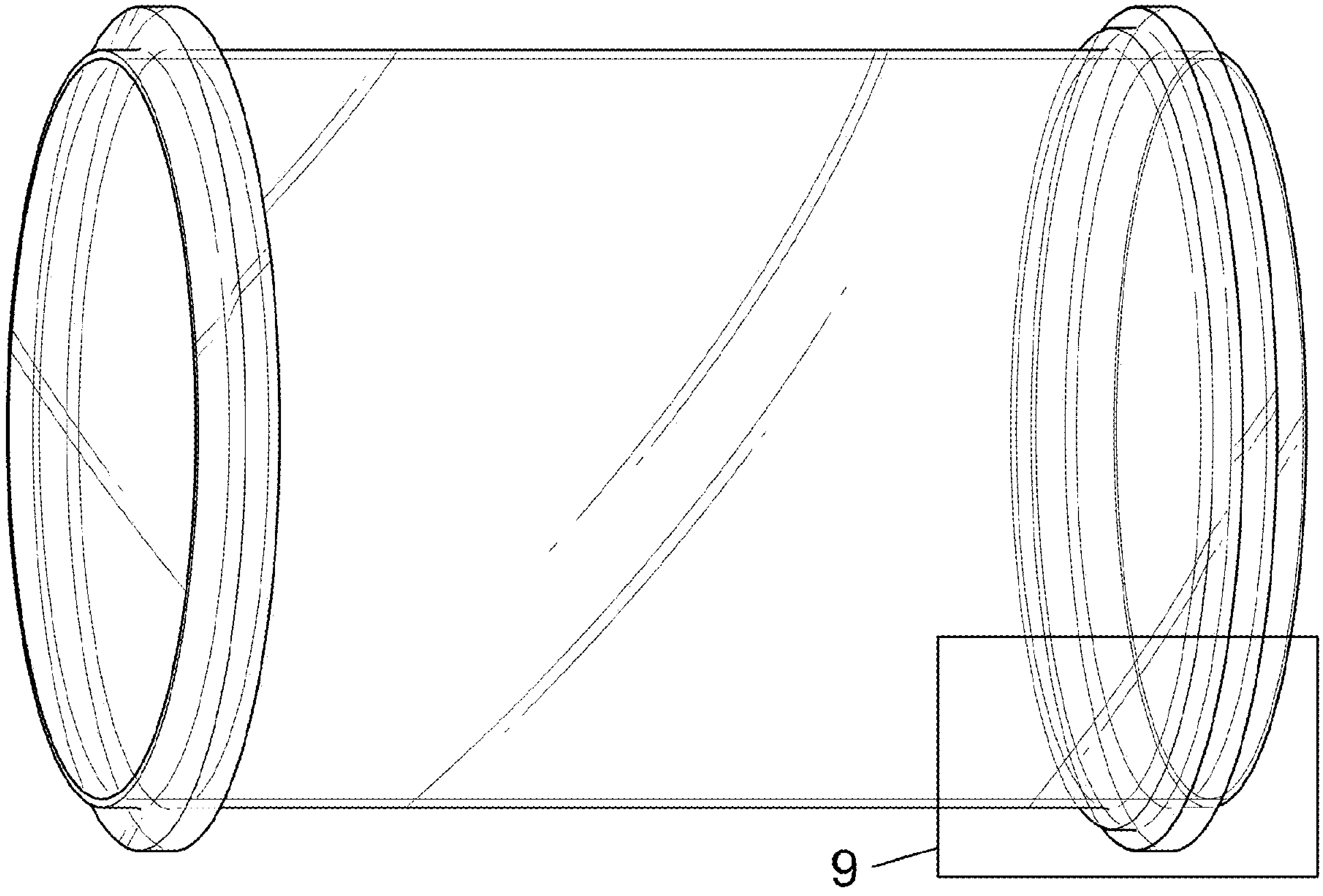

FIG. 1

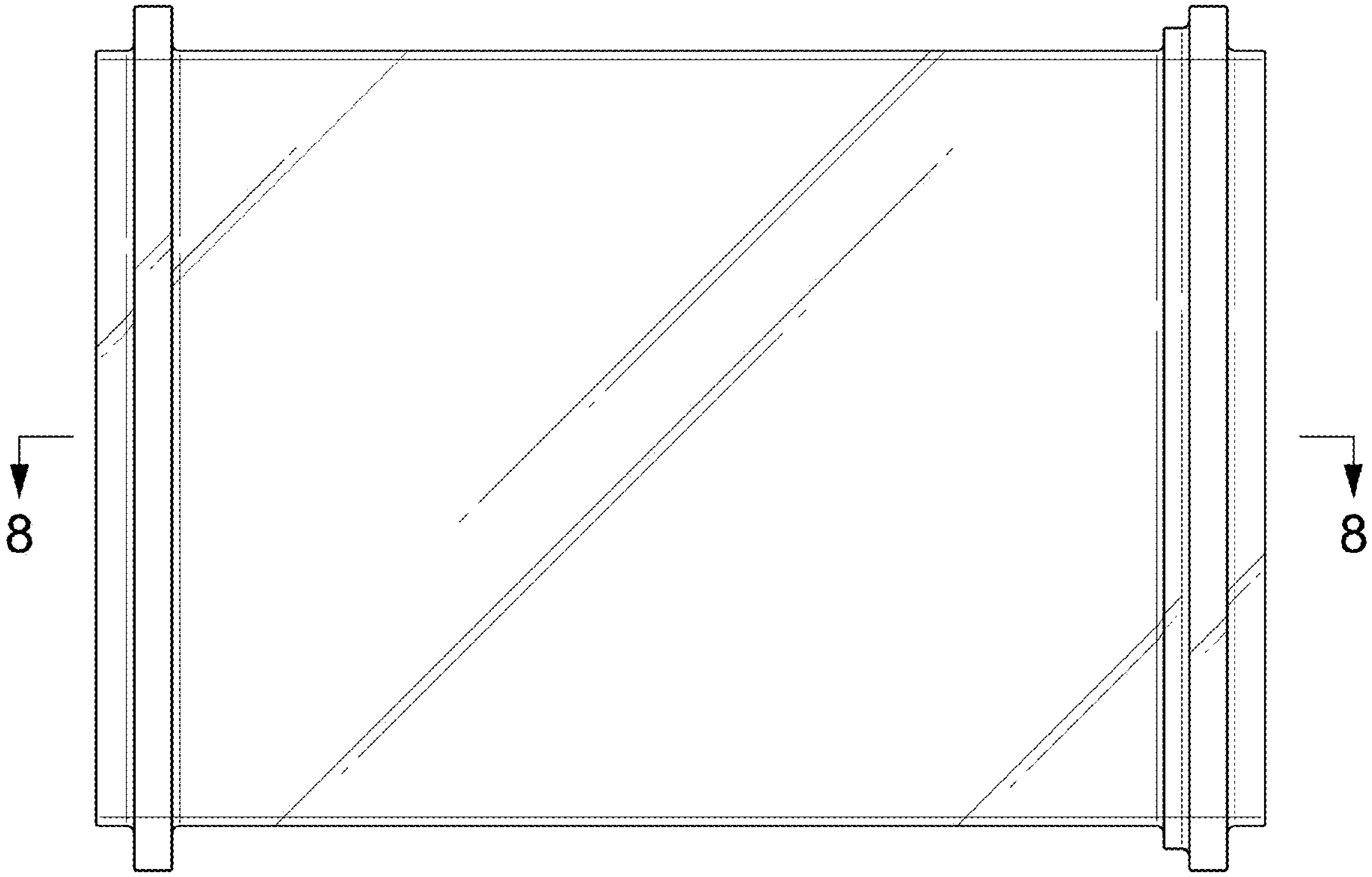

FIG. 2

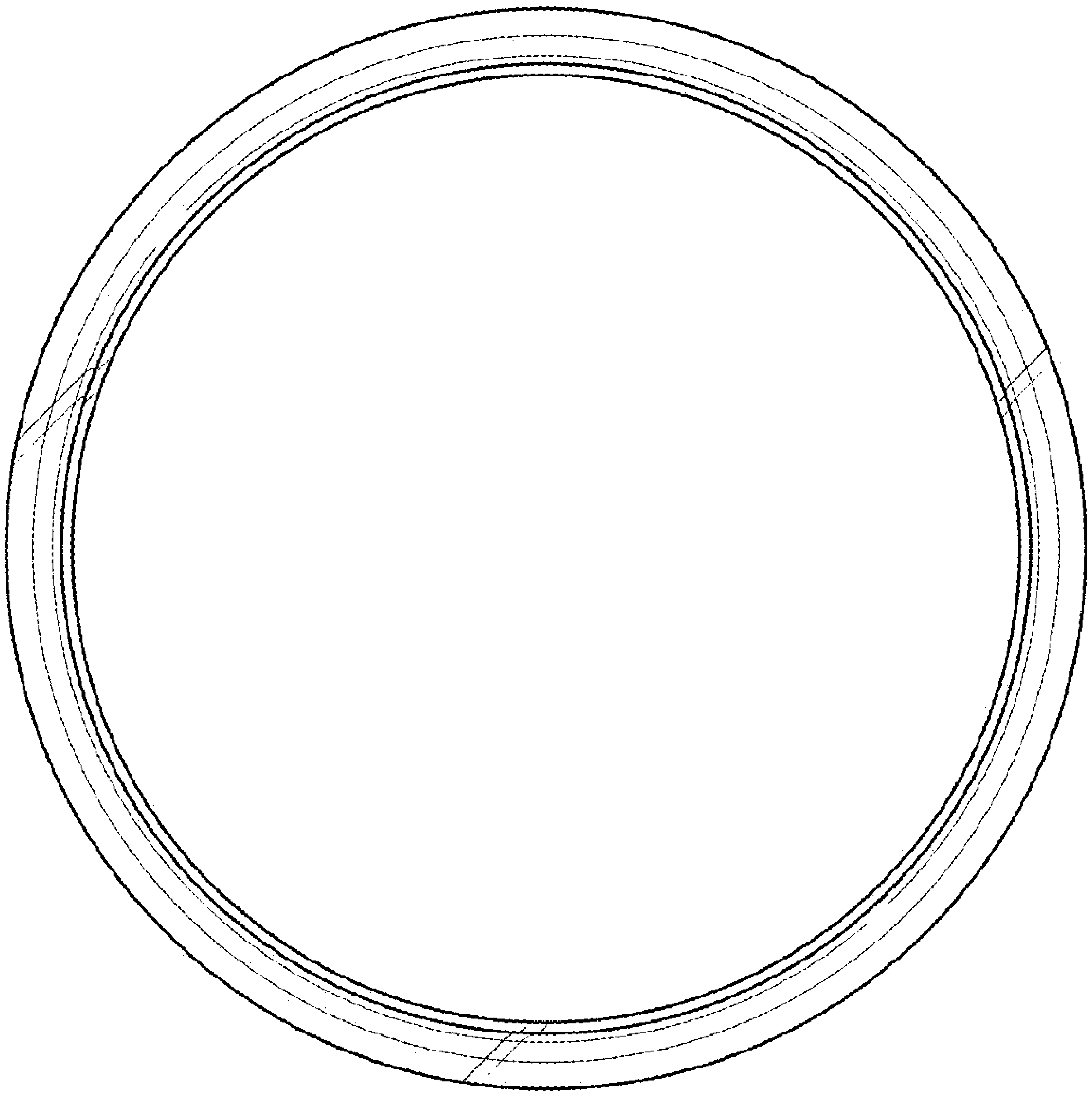

FIG. 3

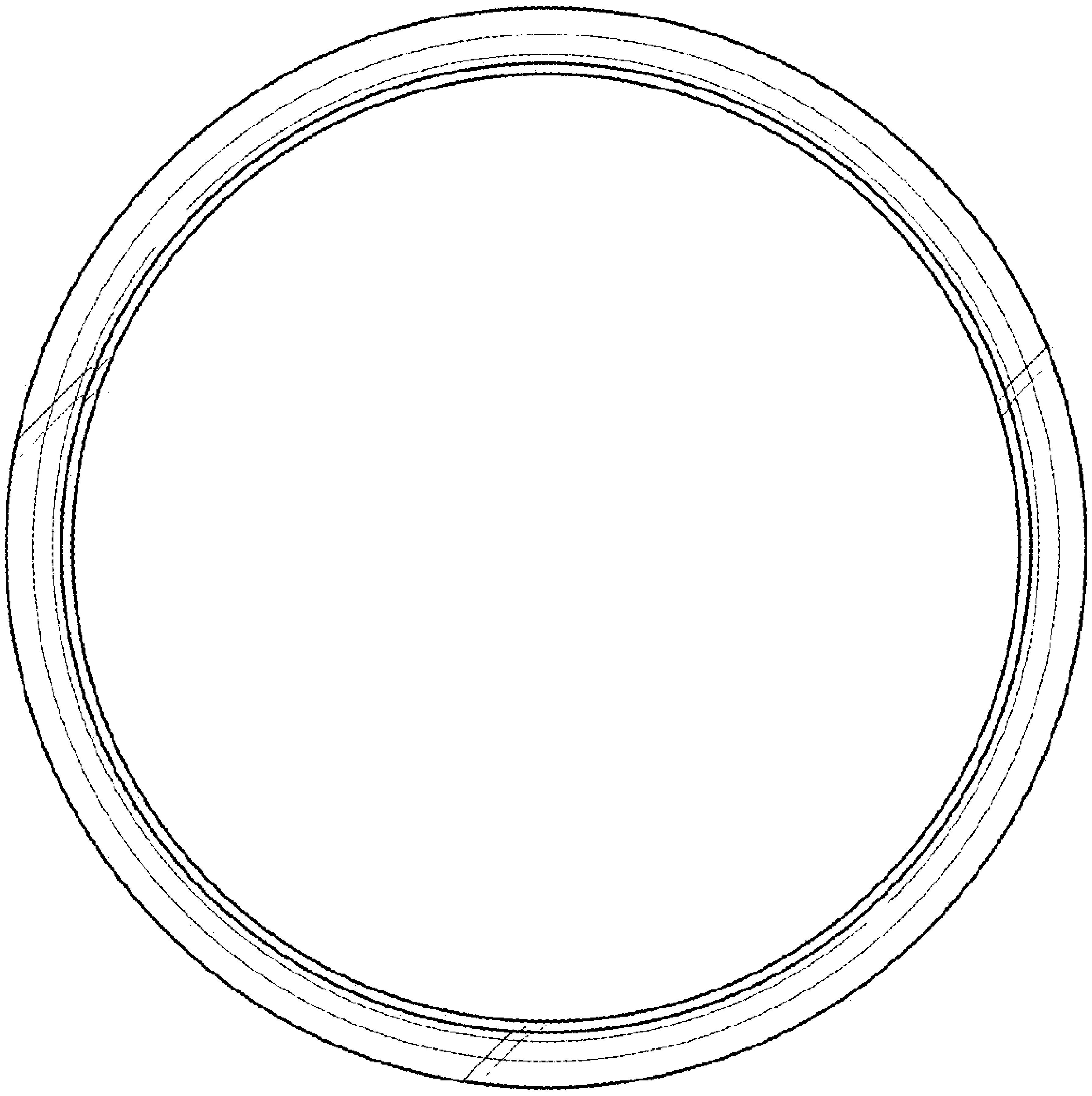

FIG. 4

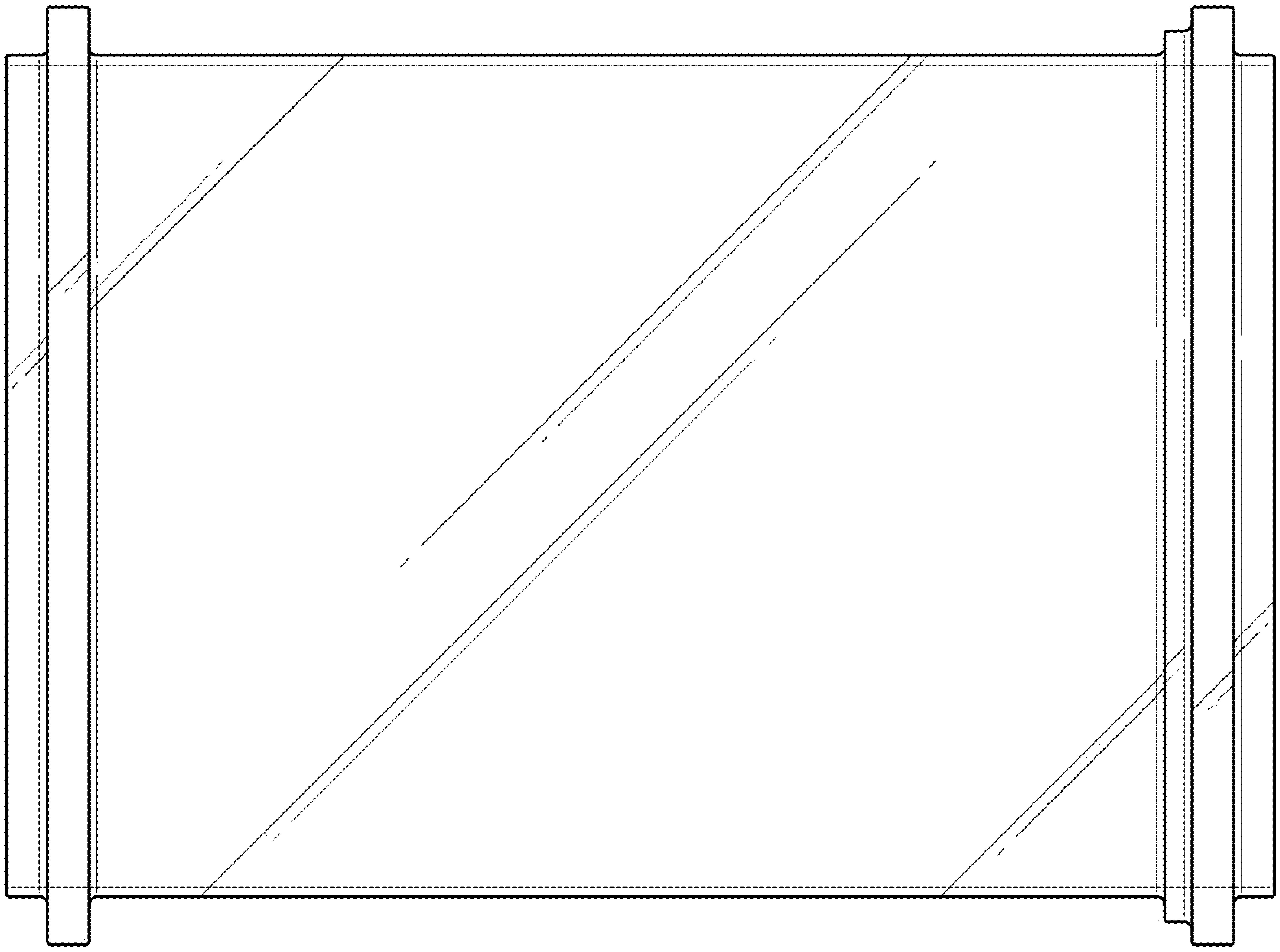

FIG. 5

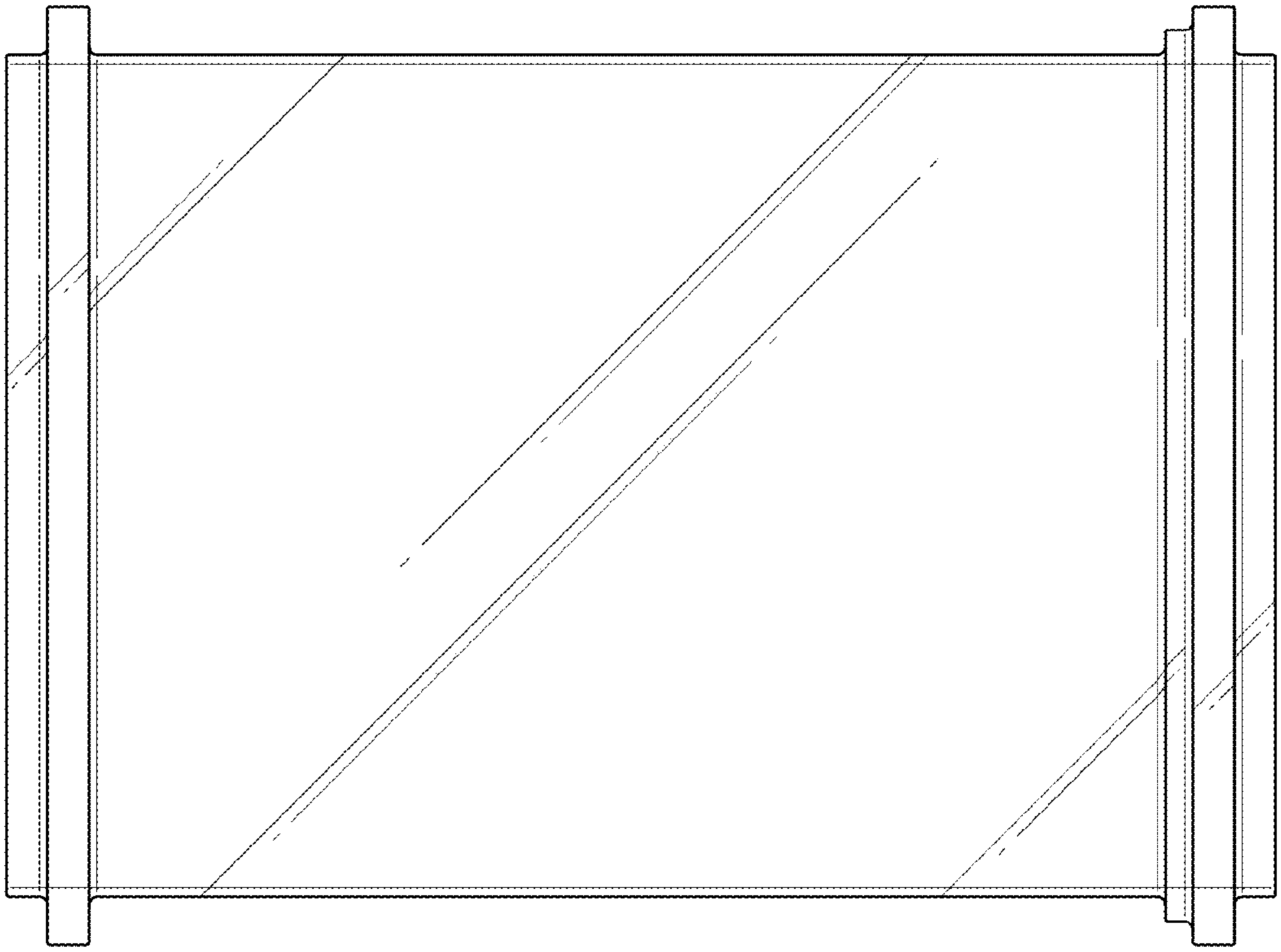

FIG. 6

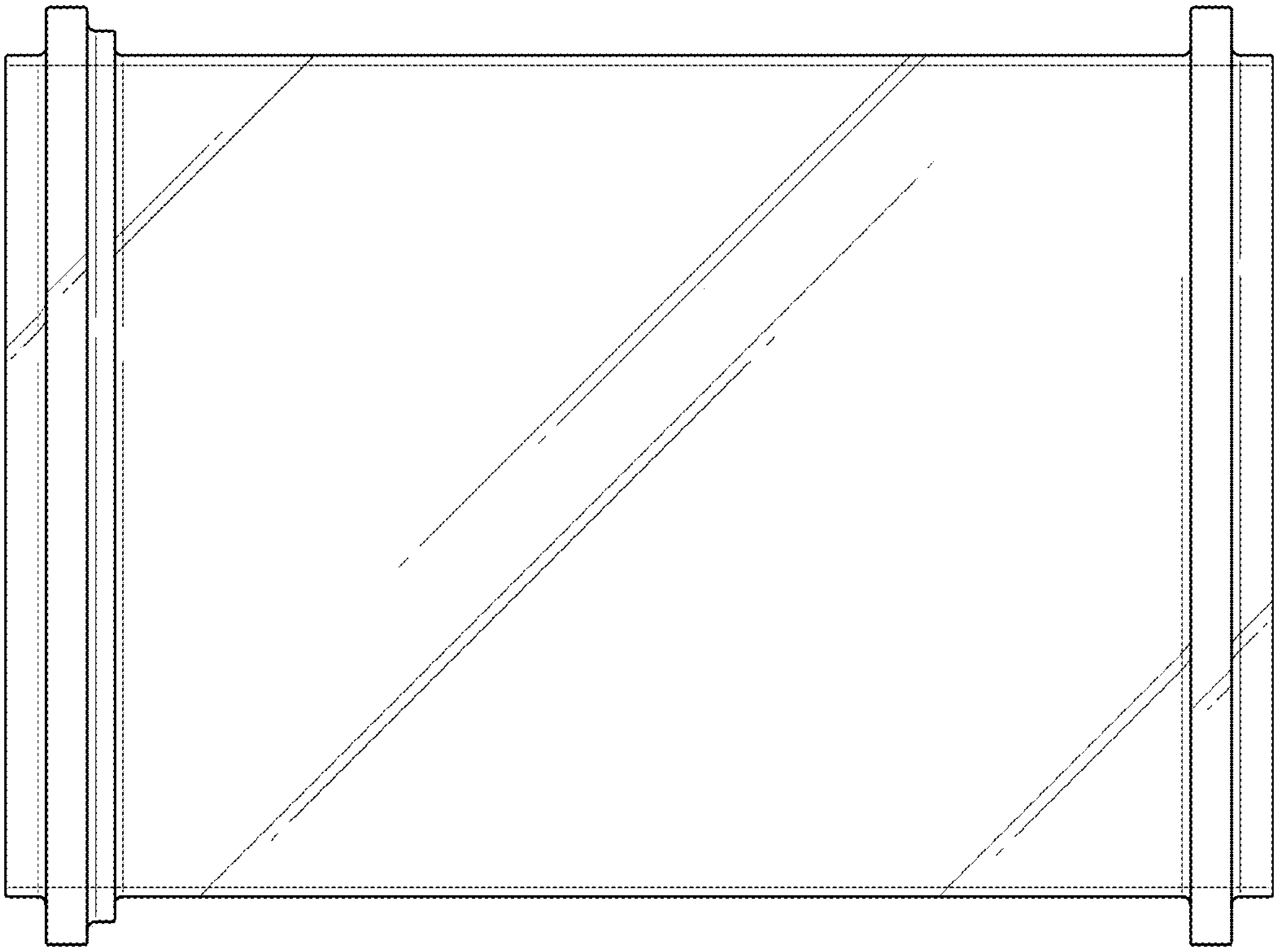

FIG. 7

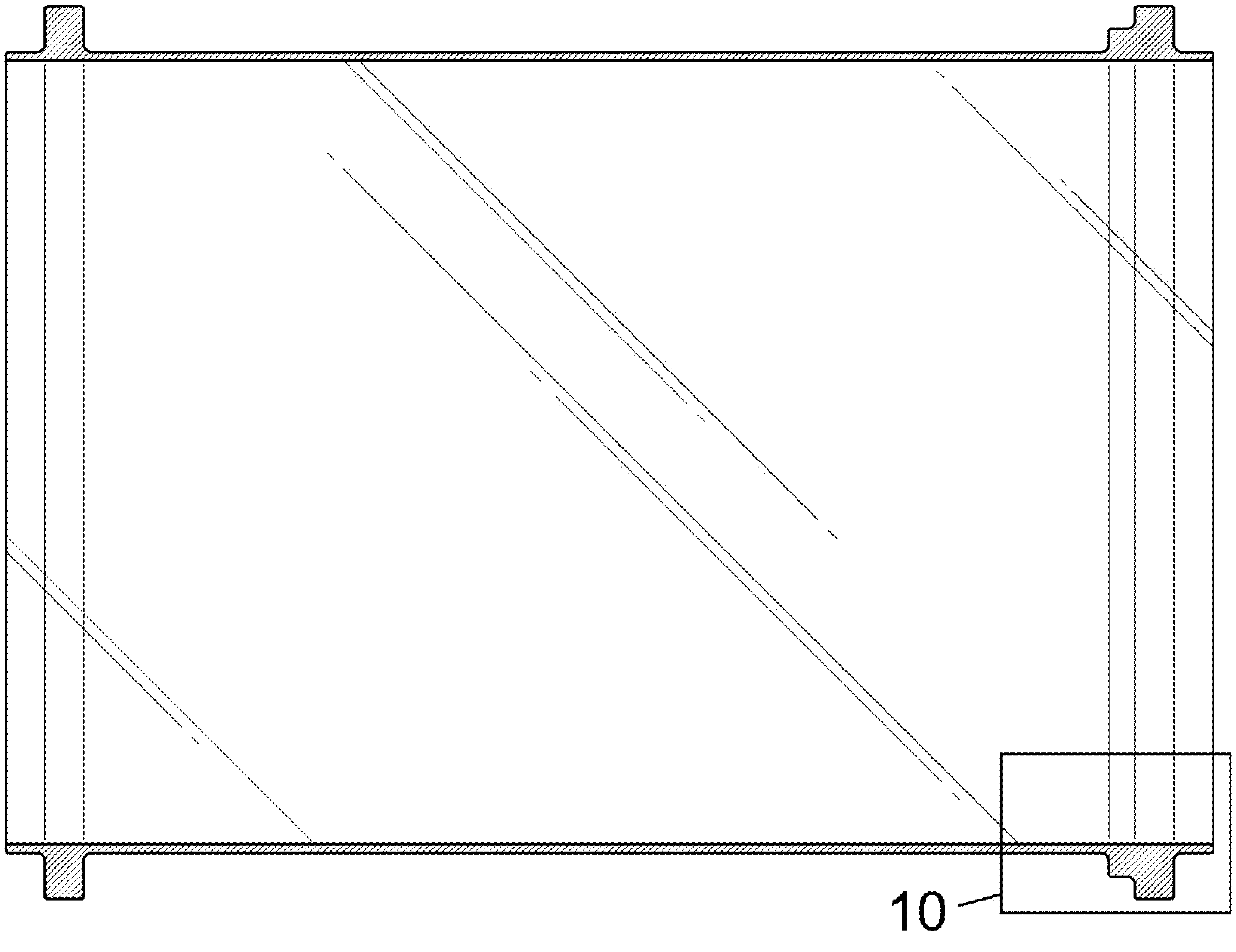

FIG. 8

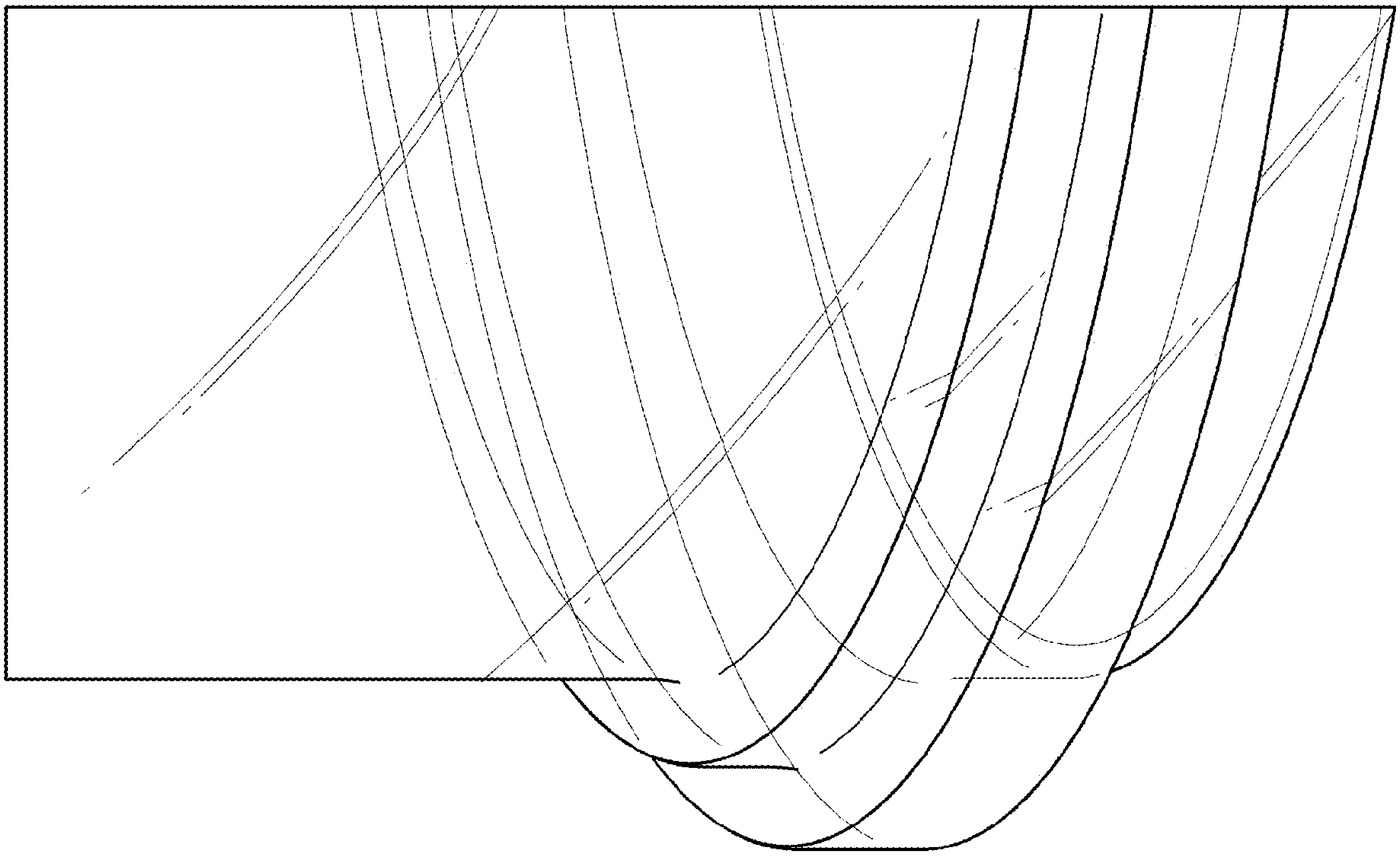

FIG. 9

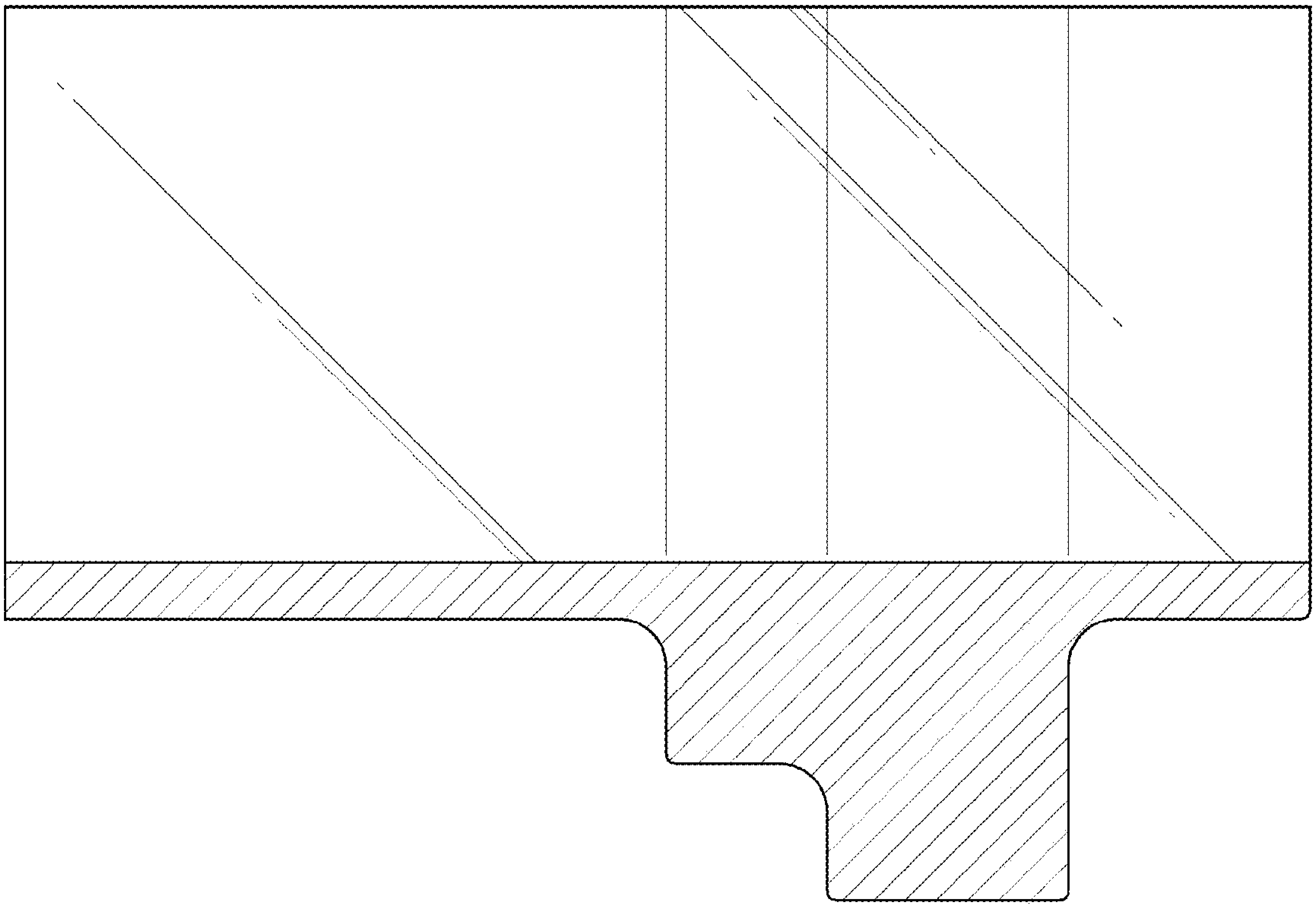

FIG. 10